

CLEAN-COPY OF CLAIMS AS AMENDED HEREIN

22. A method of spin-coating a semiconductor substrate, comprising the steps of:
- (a) dropping coating material onto a semiconductor substrate;
  - (b) rotating said semiconductor substrate about a center thereof; and
  - (c) generating an electric field circumferentially around said semiconductor substrate and said coating material, said electric field having an electric polarity opposite to an electric polarity of said coating material.